ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18 O / Stylesheet Version v18.0

> Title of Invention

Sacrificial Surfactanated Pre-Wet for Defect Reduction in a Semi-Conductor Photolithography Developing Process

Application Number:

10/675419

Confirmation Number:

6182

First Named Applicant:

John Kulp Attorney Docket Number: CT-001

Search string:

(6117486 or 6132940 or 6147010 or 6159662

or 6402398 or 6420101).pn.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
W)	1	6117486	2000-09-12	Yoshihara]	427	240
(AUD)	2	6132940	2000-10-17	Mih et al.]	430	394
M	3	6147010	2000-11-14	Whitman]	438	782
W	4	6159662	2000-12-12	Chen et al.]	430	313
W)	5	6402398	2002-06-11	Szajewski et al.	B1	396	604
M	6	6420101	2002-07-16	Lu et al.	B1	430	326

Remarks

Note: Remarks are not for responding to an office action.

Applicants are of the opinion that no fee is due as a result of this Information Disclosure Statement. If any charges or credits are necessary to complete this communication, please apply them to Deposit Account No. 23-3000.

Signature

Examiner Name	Date			
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Sheet 1 (A) of 1																	
SUBSTITUTE FOR APTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE										ATTY. CT-00	DOCKET N	٥.	SERIAL NO. 10/675,419				
IIIN 0 1 too 3 INFORMATION DISCLOSURE												APPLICANT John M. Kulp					
(Use several sheets if necessary)										FILING DATE GROUP September 30, 2003 1756			P 				
U.S. PATENT DOCUMENTS																	
EXAMINER INITIAL		PATENT NUMBER					IBEI	₹	ISSUE DATE	PATENTEE		CLASS	SUBCLASS		FILING DATE IF APPROPRIATE		
MO	A.A	5	8	4	5	1	7	0	12/01/1998	Ogata		396	604		08/15/1997		
pup	A.B	6	1	3	6	5	1	4	10/24/2000	Phan et al.		430	327		01/31/2000		
nD	A.C	6	4	7	2	1	2	7	10/29/2002	Takizawa		430	322		07/12/2000		
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- A										COUNTRY OF PATENT OFFICE		CLASS	SUBCL	ASS	TRANSLATION (YES/NO)		
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OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)																	
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EXAMINER: Initial if citation considered, whether or not in conformance. Draw line through citation only if not in conformance and not considered. Include a copy of this form with next communication to Applicant.																	